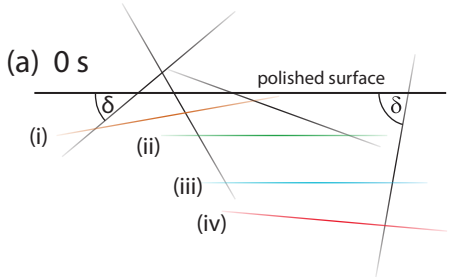
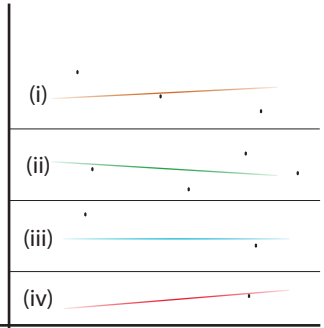
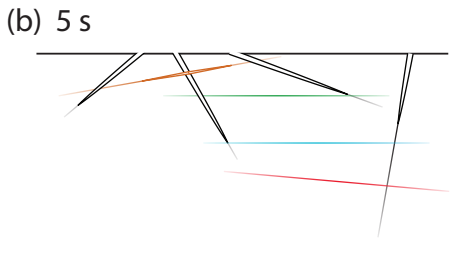
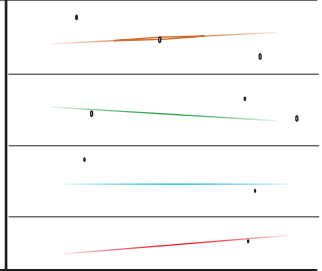
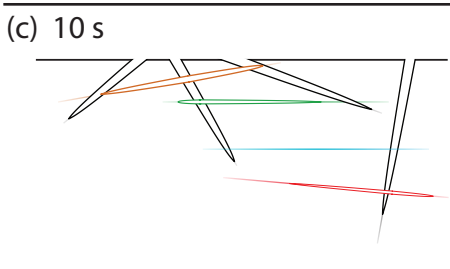
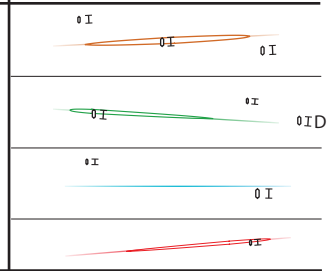
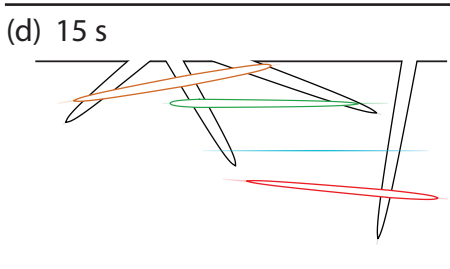
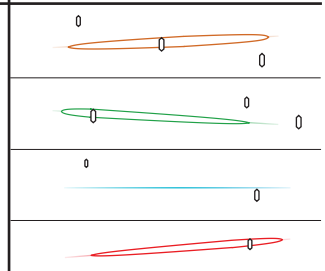
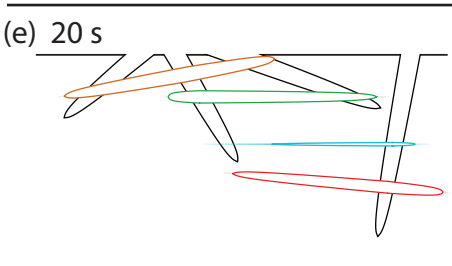
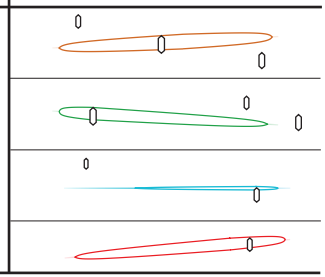
Side view	Overhead section view	Notes
		Tracks occur at all dip angles δ to polished surface $P(\delta) \propto \cos \delta$. Probability of surface crossing equal to vertical component $P(\text{cross}\|\delta) \propto L \sin \delta$. Surface crossing point is random along track. Potentially measured confined tracks dip up to 25°
		Semi-tracks etch according to $v_T(x)$ and surface crossing point. Etching channels widen at bulk etch rate v_B (simplified here as isotropic). Confined tracks are revealed when intersected by widening semi-tracks.
		Confined track-etch rates depend on intersection point and $v_T(x)$. Probability of confined track intersection at a given depth and time step is proportional to increase in sum of semi-track diameters perpendicular to track: $P(\text{int}\|z,t) \propto \Sigma D(z,t) - \Sigma D(z,t\text{-}1)$.
		As etch rate slows near track end, etched tip widens, becoming easier to see and measure.
		New tracks are intersected continuously. Continued etching may cause some originally confined tracks to cross surface.